

# Simulation Analysis of AlGa<sub>N</sub>/BGa<sub>N</sub> Based Deep Ultraviolet-A Light Emitting Diodes with Graded Step Electron Barrier Layer

Aruna Dore<sup>1</sup>, M. Manikandan<sup>1</sup>, G. Dhivyasri<sup>2</sup>, M.G. Sumithra<sup>3</sup> and R. Manaswini<sup>1\*</sup>

<sup>1</sup>Department of Electronics and Communication Engineering, Presidency University, Bengaluru, Karnataka, India

<sup>2</sup>Department of Computer Science Engineering (Data Science), Sai Vidya Institute of Technology, Bengaluru, Karnataka, India

<sup>3</sup>Department of Electronics and Communication Engineering, Sri Krishna College of Technology, Coimbatore, Tamil Nadu, India

## \*Correspondence to:

R. Manaswini

Department of Electronics and Communication Engineering,  
Presidency University,  
Bengaluru, Karnataka, India.

E-mail: manaswikirshna20@gmail.com

Received: October 11, 2023

Accepted: December 19, 2023

Published: December 22, 2023

**Citation:** Dore A, Manikandan M, Dhivyasri G, Sumithra MG, Manaswini R. 2023. Simulation Analysis of AlGa<sub>N</sub>/BGa<sub>N</sub> Based Deep Ultraviolet-A Light Emitting Diodes with Graded Step Electron Barrier Layer. *NanoWorld J* 9(S5): S109-S112.

**Copyright:** © 2023 Dore et al. This is an Open Access article distributed under the terms of the Creative Commons Attribution 4.0 International License (CCBY) (<http://creativecommons.org/licenses/by/4.0/>) which permits commercial use, including reproduction, adaptation, and distribution of the article provided the original author and source are credited.

Published by United Scientific Group

## Abstract

This study designs and analyses step-graded alternating barriers of Aluminum Gallium Nitride/Boron Gallium Nitride (AlGa<sub>N</sub>/BGa<sub>N</sub>) in the multiple quantum well (MQW) light-emitting diodes (LEDs). The graded stepwise electron blocking layer (EBL) was introduced in DUV (Deep-ultraviolet)-LED with a luminosity wavelength of 360 nm(EBL). The silicon carbide substrate used in the device is also significant for the device's better optical performance owing to its reduced polarization effect, improved crystal structure, and high thermal conductivity.

## Keywords

Boron, Ga<sub>N</sub>, Light-emitting diodes, AlGa<sub>N</sub>, Multiple quantum well

## Introduction

AlGa<sub>N</sub>-based DEP-LEDs have become popular in recent years due to their protection in the environment, high reliability, quick response, less power consumption, and lightweight portable structure. They are also used extensively in the fields of light curing, sterilization, and disinfection of viruses and germs [1-4]. DUV-LED irradiation has drawn increased attention as a more eco-friendly, secure, and safe disinfection treatment since the COVID-19 epidemic in 2019 [5, 6]. The COVID-19 virus has been shown to be killed by UV-LED irradiation in under one second [7]. DUV-A LEDs have many pros, but there are also a lot of drawbacks when it comes to research and development, including challenges with chip packaging and epitaxial growth, light extraction rates, and both internal and efficiencies below 20% of the conventional LED. For these reasons, it is challenging to widely utilize DUV-LEDs. Aluminum is typically doped with Ga<sub>N</sub> during the epitaxial growth process in order to widen the bandgap and reduce the luminescence wavelength. Although a rise in the aluminum concentration in quantum wells (QWs) increases the dislocation density also has a large polarization impact that lowers the recombination rate of the radiative factor [8].

In contrast, the magnesium acceptor's activation energy is about 500 meV in p-type doped AlGa<sub>N</sub> based DUV-LEDs, making it harder to activate, directly contributing to a poor hole-injection rate. Additionally, one of the factors contributing to the poor performance of DUV LEDs is a significant electron leakage caused by a mismatch in the carrier injection [9] and by the effects due to polarization [10]. One of the main issues with using DUV LEDs is the efficiency reduction resulting from all these problems. Peak EQE for AlGa<sub>N</sub>-based DUV LEDs occurs at currents under 20 mA, and as the current increases, the efficiency rapidly declines [11-13].

One typical approach to reducing electron leakage is to add a layer of AlGaN with a larger bandgap between the p-region and the quantum barrier in the last (LQB) to control spill-over issues in the active region. But this approach has several drawbacks. The lower energy band corner of the LQB/EBL interface drops when positive polarization charges are present, which is not advantageous for preventing electron leakage. Since a higher aluminum component causes a stronger charge polarization and a larger energy band drop, increasing the aluminum component of the EBL is not very effective [14].

Additionally, the EBL has an impact on the injection of holes even if it can successfully confine electrons to the active zone. Designing EBL structures may improve hole injection and electron blocking. The EQE is now around 20%, and the efficiency of DUV-LEDs are at lesser levels [15]. Numerous studies have looked at solutions to the issue, suggesting EBL structures through simulations and experimental research, to stabilize the electron and hole concentration.

With the help of simulations, So et al. looked into the issues of a step graded EBL design on a DUV-LED. The results depict that the device significantly outperforms a DUV-LED with a conventional EBL structure in terms of performance [16]. Mondal et al. improved the EBL structure by including a step superlattice structure to enhance the performance of a DUV-LED. Simulation studies showed the new structure's intensity of the quantum efficiency (IQE) improved by 15% and its efficiency droop drop by 15% when compared to the normal EBL structure at a 70 A/cm<sup>2</sup> current density [17].

Wang et al. developed an EBL with W-shape and an M-shaped hole-blocking region in order to enhance the recombination rate of radiative factor and efficiency [18]. Shi et al. created an irregular sawtooth hole barrier layer and EBL to regulate the distribution of carriers, enhance the recombination rate of the radiative factor, and increase the IQE [19]. By reducing electron carrier leakage in the p-side and increasing the holes injection into the recombination area, all of the aforementioned topologies increase the recombination rate and efficiency.

## Experimentation

### Device structure

Figure 1 depicts a GaN LED representation. Doping of p-type AlGaN barrier is at a range of  $5 \times 10^{19} \text{ cm}^{-3}$  is present at the anode area of the LED, which typically has a GaN cap of about 100 nm thickness. As a result, EBLs are roughly 300 nm thick. As a result, 4 GaN layers with 3 nm thick BGaN well layers are used to create 4 QWs. AlGaN barrier layers that are 7 nm thick are also formed in the structure furthermore to this effect. A  $3 \times 10^{18} \text{ cm}^{-3}$  n-doped GaN layer and an AlGaN layer with a thickness of 100 nm are produced in the cathode region. As a result, the contact terminals of the LEDs are connected to n- and p-doped GaN, respectively. GaN LEDs p-doped and n-doped anodes and cathodes serve as the ohmic contact points. The GaN well is positioned to contain the electrons. The trapping effect must be considered for better optical and electrical parameters of the result [19]. Table 1 presents device parameters with dimensions.

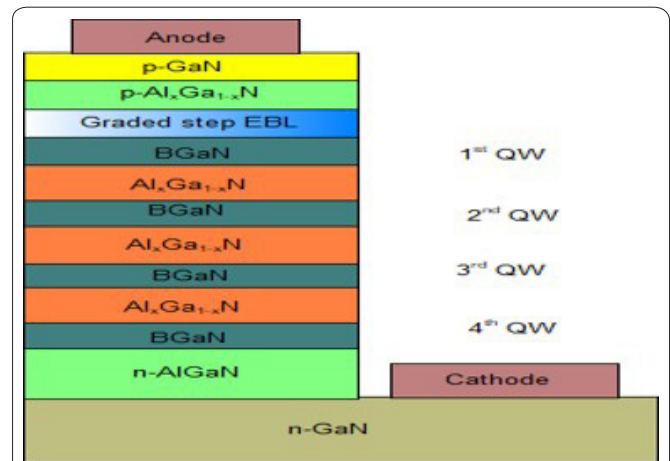


Figure 1: Schematic representation of AlGaN/BGaN MQW LED.

Table 1: Device parameters with dimensions.

Parameter	Dimensions
GaN cap layer	100 nm
p-GaN barrier	300 nm
Graded step EBL	30 nm
GaN well	3 nm
AlGaN barrier	7 nm
n-AlGaN	100 nm
n-doping	$3 \times 10^{18} \text{ cm}^{-3}$
p-type doping	$5 \times 10^{19} \text{ cm}^{-3}$

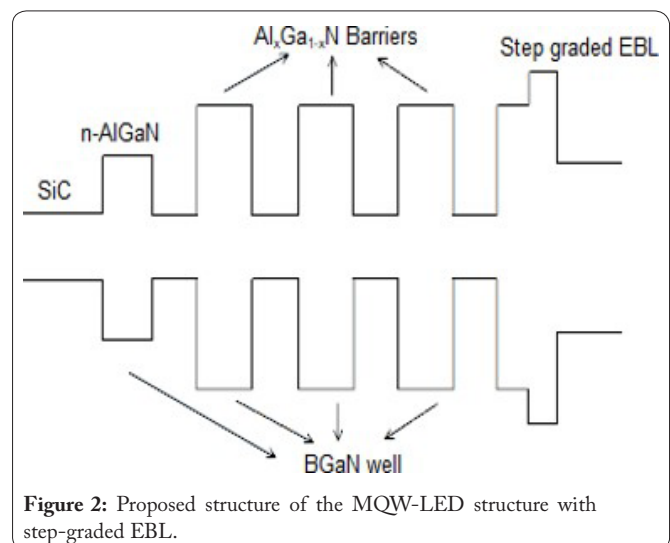


Figure 2: Proposed structure of the MQW-LED structure with step-graded EBL.

Figure 2 presents proposed structure of the MQW-LED structure with step-graded EBL. A 50 nm p-type GaN capping region is placed above the active region with a magnesium concentration of  $5 \times 10^{19} \text{ cm}^{-3}$  and a 30 nm thick p-type  $\text{Al}_{0.15}\text{Ga}_{0.85}\text{N}$  EBL is deposited. Other material characteristics for the study are derived from [20], and the device dimension is proposed in a rectangular shape measuring 1 x 1 mm.

## Results and Discussion

Figure 3 depicts the luminance power relative to the anode voltage. The anode voltage causes a rise in the observed luminous power. Figure 4 shows the power spectral density over the emission wavelength. A top point in the power spectra

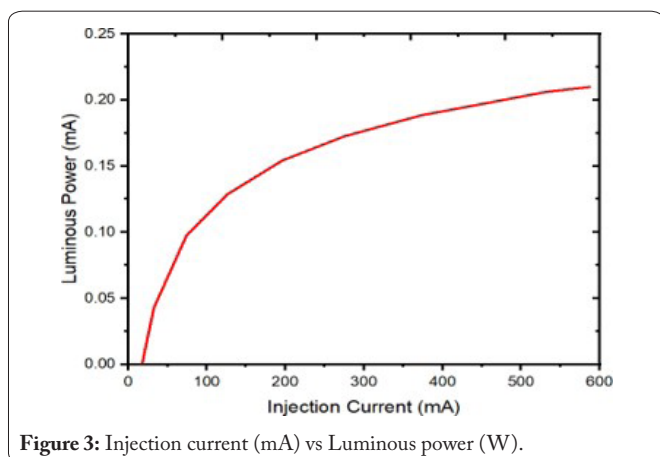


Figure 3: Injection current (mA) vs Luminous power (W).

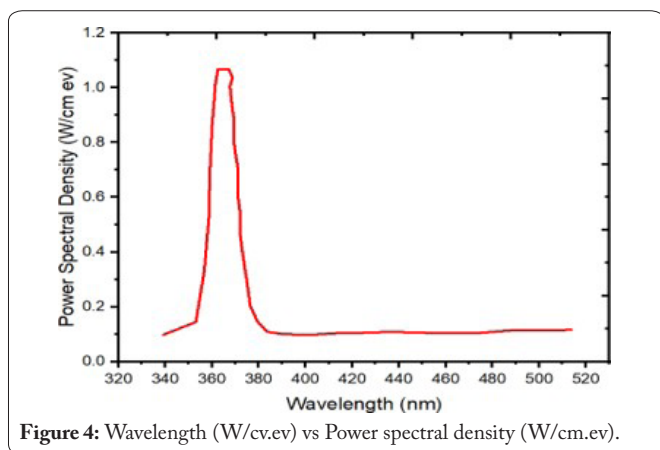


Figure 4: Wavelength (W/cv.ev) vs Power spectral density (W/cm.ev).

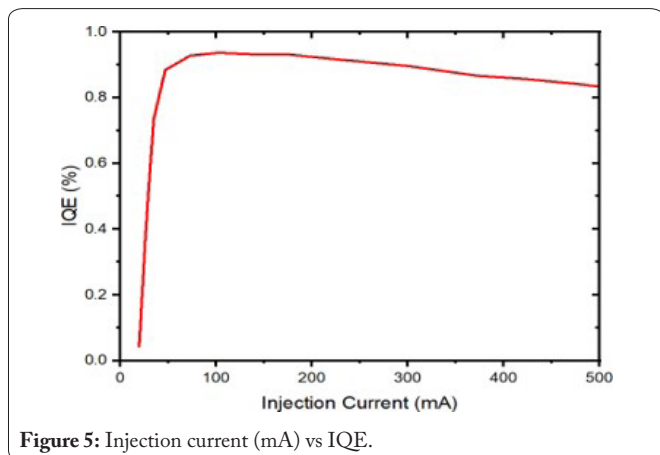


Figure 5: Injection current (mA) vs IQE.

is seen at 360 nm in wavelength. The UV emission of photons from the boron-based GaN well LED device is shown by the spike at 360 nm [21-22]. Figure 5 shows the IQE of a step graded B GaN well LED. IQE increases with injection current when the injection current is low. It then reaches saturation and exhibits efficiency droop.

## Conclusion

The LED with boron-doped GaN QW and step-graded EBL was studied in this article. A TCAD simulator is used to investigate the LED, and performance is examined. Simulation results depict the high hole injection due to the

p-type GaN barrier near step graded EBL in the device design, which reduces the lattice mismatching between boron based GaN QW and AlGaIn step-graded EBL. Therefore, the boron doped GaN LED is an excellent device for lighting applications.

## Acknowledgements

None.

## Conflict of Interest

None.

## References

1. Mondal RK, Chatterjee V, Pal S. 2020. AlInGaIn-based superlattice p-region for improvement of performance of deep UV LEDs. *Opt Mater* 104: 109846. <https://doi.org/10.1016/j.optmat.2020.109846>
2. Shatalov M, Lunev A, Hu X, Bilenko O, Gaska I, et al. 2012. Performance and applications of deep UV LED. *Int J High Speed Electron Syst* 21(01): 1250011. <https://doi.org/10.1142/S0129156412500115>
3. Liu N, Gu H, Wei Y, Zheng S. 2020. Performance enhancement of AlGaIn-based deep ultraviolet light-emitting diodes by using stepped and super-lattice n-type confinement layer. *Superlattices Microstruct* 141: 106492. <https://doi.org/10.1016/j.spmi.2020.106492>
4. Li Y, Chen S, Tian W, Wu Z, Fang Y, et al. 2013. Advantages of AlGaIn-based 310-nm UV light-emitting diodes with Al content graded AlGaIn electron blocking layers. *IEEE Photonics J* 5(4): 8200309. <https://doi.org/10.1109/JPHOT.2013.2271718>
5. Usman M, Malik S, Khan MA, Hirayama H. 2021. Suppressing the efficiency droop in AlGaIn-based UVB LEDs. *Nanotechnology* 32(21): 215703. <https://doi.org/10.1088/1361-6528/abe4f9>
6. Liao Y, Li D, Guo Q, Liu Y, Wang H, et al. 2021. Temperature-dependent study on AlGaIn-based deep ultraviolet light-emitting diode for the origin of high ideality factor. *AIP Adv* 11: 105214. <https://doi.org/10.1063/5.0059256>
7. Liu S, Luo W, Li D, Yuan Y, Tong W, et al. 2021. Sec eliminating the SARS-CoV-2 by AlGaIn based high power deep ultraviolet light source. *Adv Funct Mater* 31(7): 2008452. <https://doi.org/10.1002/adfm.202008452>
8. Kwon MR, Park TH, Lee TH, Lee BR, Kim TG. 2018. Improving the performance of AlGaIn-based deep-ultraviolet light-emitting diodes using electron blocking layer with a heart-shaped graded Al composition. *Superlattices Microstruct* 116: 215-220. <https://doi.org/10.1016/j.spmi.2018.02.033>
9. El-Ghoroury HS, Yeh M, Chen JC, Li X, Chuang CL. 2016. Growth of monolithic full-color GaN-based LED with intermediate carrier blocking layers. *AIP Adv* 6: 075316. <https://doi.org/10.1063/1.4959897>
10. Bao X, Sun P, Liu S, Ye C, Li S, et al. 2015. Performance improvements for AlGaIn-based deep ultraviolet light-emitting diodes with the p-type and thickened last quantum barrier. *IEEE Photonics J* 7(1): 1400110. <https://doi.org/10.1109/JPHOT.2014.2387253>
11. Shatalov M, Sun W, Lunev A, Hu X, Dobrinsky A, et al. 2012. AlGaIn deep-ultraviolet light-emitting diodes with external quantum efficiency above 10%. *Appl Phys Express* 5(8): 082101. <https://doi.org/10.1143/APEX.5.082101>
12. Takano T, Mino T, Sakai J, Noguchi N, Tsubaki K, et al. 2017. Deep-ultraviolet light-emitting diodes with external quantum efficiency higher than 20% at 275 nm achieved by improving light-extraction efficiency. *Appl Phys Express* 10(3): 031002. <https://doi.org/10.7567/APEX.10.031002>
13. Manikandan M, Nirmal D, Ajayan J, Mohankumar P, Prajoon P, et al. 2019. A review of blue light emitting diodes for future solid state light-

- ing and visible light communication applications. *Superlattices Microstruct* 136: 106294. <https://doi.org/10.1016/j.spmi.2019.106294>
14. Ji X, Wei T, Yang F, Lu H, Wei X, et al. 2014. Efficiency improvement by polarization-reversed electron blocking structure in GaN-based Light-emitting diodes. *Opt Express* 22(103): A1001-A10088. <https://doi.org/10.1364/OE.22.0A1001>
  15. Shi L, Du P, Tao G, Liu Z, Luo W, et al. 2021. High efficiency electron-blocking-layer-free deep ultraviolet LEDs with graded Al-content AlGaIn insertion layer. *Superlattices Microstruct* 158: 107020. <https://doi.org/10.1016/j.spmi.2021.107020>
  16. So B, Kim J, Kwak T, Kim T, Lee J, et al. 2018. Improved carrier injection of AlGaIn-based deep ultraviolet light emitting diodes with graded superlattice electron blocking layers. *RSC Adv* 8(62): 35528-35533. <https://doi.org/10.1039/C8RA06982D>
  17. Mondal RK, Chatterjee V, Pal S. 2019. Effect of step-graded superlattice electron blocking layer on performance of AlGaIn based deep-UV light emitting diodes. *Phys E Low Dimens Syst Nanostruct* 108: 233-237. <https://doi.org/10.1016/j.physe.2018.11.022>
  18. Wang L, He W, Zheng T, Chen Z, Zheng S. 2019. Enhanced optical performance of AlGaIn-based deep-ultraviolet light-emitting diode with m-shaped hole blocking layer and w-shaped electron blocking layer. *Superlattices Microstruct* 133: 106188. <https://doi.org/10.1016/j.spmi.2019.106188>
  19. Shi H, Gu H, Li J, Yang X, Zhang J, et al. 2019. Performance improvements of AlGaIn-based deep-ultraviolet light-emitting diodes with specifically designed irregular sawtooth hole and electron blocking layers. *Opt Commun* 441: 149-154. <https://doi.org/10.1016/j.optcom.2019.02.054>
  20. Manikandan M, Nirmal D, Ajayan J, Arivazhagan L, Prajoon P, et al. 2022. Physics based modeling of AlGaIn/BGaIn quantum well based ultra violet light emitting diodes. *Opt Quantum Electron* 54(3): 168. <https://doi.org/10.1007/s11082-022-03552-8>
  21. Dhivyasri G, Nirmal D, Manikandan M, Gokiladeepa G, Ajayan J, et al. 2022. Simulation and comparison of AlGaIn LEDs with boron doped GaIn well using assorted aluminium concentration. In IEEE International Conference on Nanoelectronics, Nanophotonics, Nanomaterials, Nanobioscience & Nanotechnology, Kottayam, Kerala, India.
  22. Manikandan M, Nirmal D, Dhivyasri G, Arivahagan L, Ajayan J, et al. 2021. Simulation analysis of UV-A band LEDs with BGaIn single quantum well using SiC substrate for medical applications. In 3<sup>rd</sup> International Conference on Signal Processing and Communication, Coimbatore, Tamil Nadu, India.